Amendments to the Claims:

The following listing of claims replaces all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1-2. (Canceled)
- 3. (Currently Amended) A fluorine-containing cyclic compound represented by the following general formula (3):

[Chemical Formula 32]

$$R_6$$
 R_7
 R_8
 CF_3
 R_4
 CF_3
 R_1
 CF_3
 R_2
 R_3
 R_3

in the general formula (3), wherein

R1b is a C_1 - C_{25} cyclic alkyl group, cyclic alkenyl group, cyclic alkynyl group, aryl group, or heterocyclic group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond;

each of R2 to R7 is independently a hydrogen atom, a halogen atom, or a C₁-C₂₅ straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond; and

R8 is a carbonyl group or methylene group, or a single bond.

4-5. (Canceled)

6. (Currently Amended) A fluorine-containing cyclic compound <u>according to claim 3, which is represented by the following general formula (6):</u>
[Chemical Formula 35]

$$R_{6}$$
 R_{7}
 R_{8}
 R_{12}
 R_{10}
 R_{4}
 CF_{3}
 R_{15}
 R_{13}
 R_{11}
 R_{11}
 R_{12}
 R_{10}
 R_{4}
 R_{4}
 R_{5}
 R_{8}
 R_{8}
 R_{10}
 R_{10}
 R_{10}
 R_{10}
 R_{10}
 R_{10}
 R_{11}
 R_{12}
 R_{13}
 R_{11}
 R_{11}

in the general formula (6), wherein

each of R2 to R7 and R9 to R15 is independently a hydrogen atom, a halogen atom, or a C₁-C₂₅ straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom;

R8 is a carbonyl group or methylene group or a single bond;

R10 and R11, R12 and R13, or R14 and R15 may be bonded together to form a ring; in such case, it is an C₁-C₂₅ alkylene group that may contain oxygen, sulfur, nitrogen or hetero atom; and

"a" is 0 or 1,

"b" is an integer of 0-2, and "c" is an integer of 0-2.

7-8. (Canceled)

9. (Currently Amended) A fluorine-containing cyclic compound according to claim 3, which is represented by the following general formula (9): [Chemical Formula 38]

$$R_6$$
 R_7
 R_8
 R_4
 CF_3
 CF_3
 R_2
 R_3
 CF_3

in the general formula (9), wherein

each of R2 to R7 is independently a hydrogen atom, a halogen atom, or a C₁-C₂₅ straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom; and

R8 is a carbonyl group or methylene group or a single bond.

10. (Currently Amended) A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (10): [Chemical Formula 39]

$$R_{6}$$
 R_{7}
 R_{8}
 CF_{3}
 R_{1}
 CF_{3}
 R_{2}
 R_{3}
 R_{2}
 R_{3}
 R_{3}

in the general formula (10), R1b and R2 to R8 are defined as in claim 3 wherein

R₁b represents a C₁-C₂₅ cyclic alkyl group, cyclic alkenyl group, cyclic alkynyl group, aryl group, or heterocyclic group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond;

each of R₂ to R₇ independently represents a hydrogen atom, a halogen atom, or a C₁-C₂₅ straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond; and

R₈ represents a carbonyl group or methylene group, or a single bond.

11. (Currently Amended) A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a according to claim 10, wherein the repeating unit is represented by the following general formula (11):

[Chemical Formula 40]

$$R_{14}$$
 R_{12}
 R_{10}
 R_{4}
 R_{2}
 R_{3}
 R_{15}
 R_{13}
 R_{11}
 R_{11}
 R_{11}
 R_{12}
 R_{10}
 R_{2}
 R_{3}
 R_{11}
 R_{11}

in the general formula (11), R2 to R15 and a, b and c are defined as in claim-6 wherein

each of R₂ to R₇ and R₉ to R₁₅ independently represents a hydrogen atom, a halogen atom, or a C₁-C₂₅ straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom;

R₈ represents a carbonyl group or methylene group or a single bond;

 R_{10} and R_{11} , R_{12} and R_{13} , or R_{14} and R_{15} may be bonded together to form a ring; in such case, it is an C_1 - C_{25} alkylene group that may contain oxygen, sulfur, nitrogen or hetero atom; and

"a" is 0 or 1,

"b" is an integer of 0-2, and

"c" is an integer of 0-2.

12. (Currently Amended) A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in

comprising a according to claim 10, wherein the repeating unit is represented by the following general formula (12):

[Chemical Formula 41]

$$R_{6}$$
 R_{7}
 R_{8}
 CF_{3}
 R_{7}
 R_{8}
 CF_{3}
 R_{4}
 CF_{3}
 R_{7}
 R_{8}
 CF_{3}
 R_{7}
 R_{8}
 CF_{3}
 R_{7}
 R_{8}
 CF_{3}
 R_{7}
 R_{8}
 CF_{3}
 R_{12}
 CF_{3}
 CF_{3}

in the general formula (12), R2 to R8 are defined as in claim 9 wherein each of R2 to R7 independently represents a hydrogen atom, a halogen atom, or a C1-C25 straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom; and

R₈ represents a carbonyl group or methylene group or a single bond.

13-17. (Canceled)

- 18. (Previously Presented) A fluorine-containing polymer compound according to claim 10, which comprises a repeating unit having an acid-labile group.
- 19. (Canceled)
- 20. (Previously Presented) A resist material comprising a fluorine-containing polymer compound according to claim 10.
- 21. (Previously Presented) A chemically-amplified resist material comprising a resist material according to claim 20 and a photoacid generator.
- 22. (Previously Presented) A pattern forming process comprising the steps of:
 - (a) applying a resist material according to claim 20 to a substrate:
 - (b) subjecting the substrate to a heat treatment;
 - (c) conducting an exposure, using a high-energy ray of a wavelength of 300nm or less or an electron beam, through a photomask;
 - (d) subjecting the exposed resist film to a heat treatment; and conducting a development treatment.
- 23. (Original) A pattern forming process according to claim 22, wherein the high-energy ray used is F₂ excimer laser, ArF excimer laser, KrF excimer laser or soft X-ray.
- 24. (Previously Presented) A fluorine-containing polymer compound according to claim 10, wherein hydroxyl groups contained in the molecule are partially or entirely protected with protecting groups.